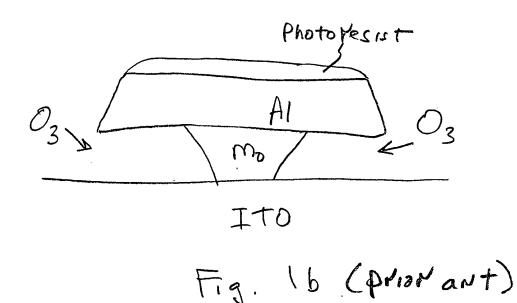


Fig. la (Prior art)



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Etch rate of Materials by O3 water (85ppm, pH3.3)

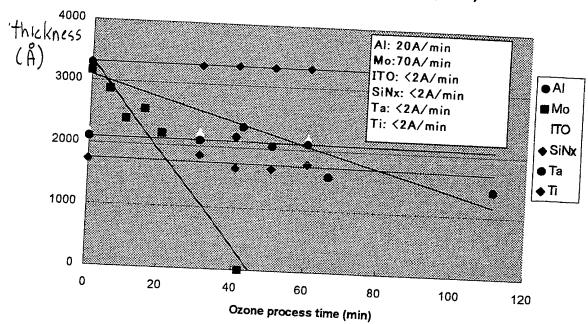
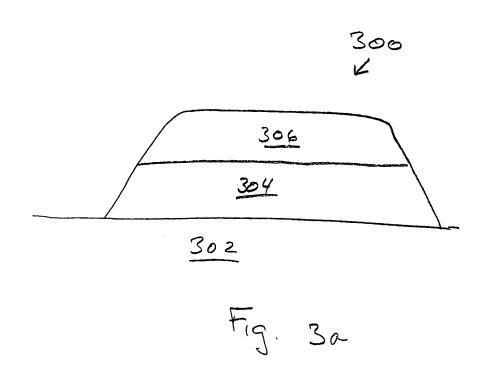
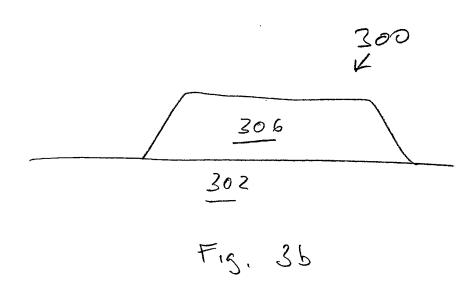


Fig. 2





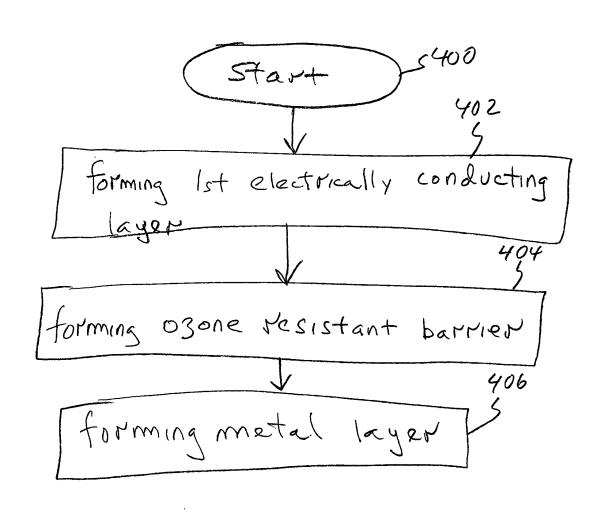


Fig. 4

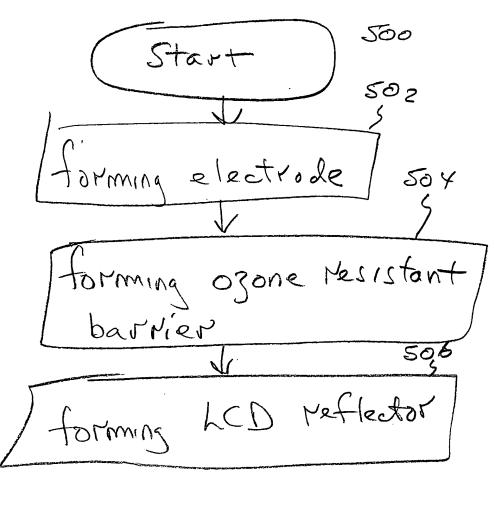


Fig. 5

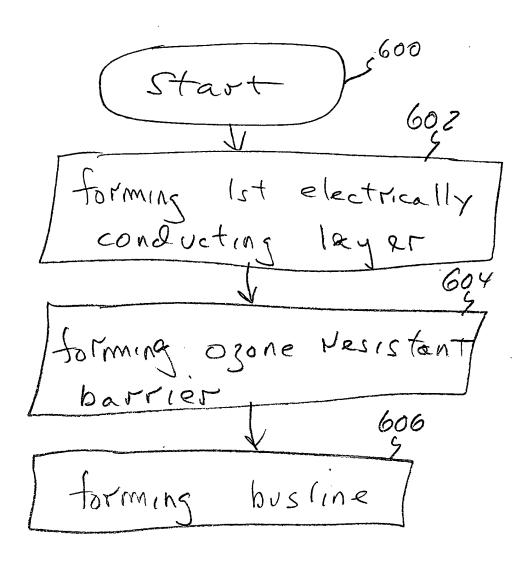


Fig. 6

STATT electrically Ozone resistant barrier metal ormine 708 2 noto resist Primaro meta etching photo resist Stripping LCD reflector leaving Fig. 7

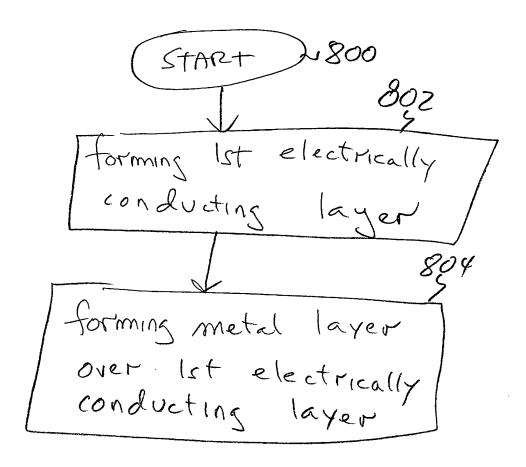


Fig. 8